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Planning

Supply and Commissioning of an Inductively Coupled Plasma Etcher

University of Strathclyde

F01: Prior information notice

Prior information only

Notice identifier: 2025/S 000-008704

Procurement identifier (OCID): ocds-h6vhtk-04eb72

Published 11 March 2025, 12:09pm

Section I: Contracting authority

I.1) Name and addresses

University of Strathclyde

Learning & Teaching Building, 49 Richmond Street

Glasgow

G1 1XU

Contact

Rene de Sousa

Email

rene.de-sousa@strath.ac.uk

Country

United Kingdom

NUTS code

UKM82 - Glasgow City

Internet address(es)

Main address

<http://www.strath.ac.uk/>

Buyer's address

https://www.publiccontractsscotland.gov.uk/search/Search_AuthProfile.aspx?ID=AA00113

I.2) Information about joint procurement

The contract is awarded by a central purchasing body

I.3) Communication

Additional information can be obtained from the above-mentioned address

I.4) Type of the contracting authority

Body governed by public law

I.5) Main activity

Education

Section II: Object

II.1) Scope of the procurement

II.1.1) Title

Supply and Commissioning of an Inductively Coupled Plasma Etcher

Reference number

UOS-36338-2025

II.1.2) Main CPV code

- 38000000 - Laboratory, optical and precision equipments (excl. glasses)

II.1.3) Type of contract

Supplies

II.1.4) Short description

An Inductively Coupled Plasma Etcher is sought to process semiconductor materials such as (but not limited to) Gallium Nitride and Silicon. The ideal system will be deployed for academic research and located within a cleanroom micro-fabrication facility.

II.1.6) Information about lots

This contract is divided into lots: No

II.2) Description

II.2.2) Additional CPV code(s)

- 31712100 - Microelectronic machinery and apparatus

II.2.3) Place of performance

NUTS codes

- UKM82 - Glasgow City

Main site or place of performance

University of Strathclyde

II.2.4) Description of the procurement

The Institute of Photonics is seeking to complement their cleanroom micro-fabrication facility equipment with an Inductively Coupled Plasma Etcher. The system will be used to process semiconductor materials typically (but not limited to) Gallium Nitride (GaN) and Silicon (Si) passive and active devices. The system will be employed for academic research. It is purposed to bring extra capability to already existing assets.

The system sought after is destined to provide the capability of chlorinated and fluorinated distinct plasma etchings. Chlorine-based etch rates for GaN should be in the order of few hundreds of nanometres per minute (c.a. 500 nm/min). Selectivity to typical masking material such as photoresist and silica (SiO₂) should be guaranteed. Fluorinated-based plasma in a Deep Reactive Ion Etching mode of Silicon should be provisioned to execute the Bosch process.

The system should allow the load-lock handling and processing of a single 4" wafer.

II.2.14) Additional information

The University is publishing this PIN for initial Market Research and Engagement purposes. The University may conduct further market engagement with the suppliers that note interest in this opportunity.

II.3) Estimated date of publication of contract notice

12 March 2025

Section IV. Procedure

IV.1) Description

IV.1.8) Information about the Government Procurement Agreement (GPA)

The procurement is covered by the Government Procurement Agreement: Yes

Section VI. Complementary information

VI.3) Additional information

NOTE: To register your interest in this notice and obtain any additional information please visit the Public Contracts Scotland Web Site at

https://www.publiccontractsscotland.gov.uk/Search/Search_Switch.aspx?ID=792877.

(SC Ref:792877)